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| Company Name | WONIK IPS |
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| Exhibitor Introduction (Within 200 words) | <p>Since its foundation in 1991, WONIK IPS has been greatly contributed to Korea's semiconductor & display equipment industry with its continuous R&D and customer satisfaction based management.</p> <p>WONIK IPS is now transforming itself to Korea's best all-process equipment company, by largely investing on the next generation technology, under the customer-based and transparency management.</p> <p>Especially for the display equipment, WONIK IPS provides core process equipment with its mass production proven technologies for AMOLED panel such as Dry etcher, Evaporator and PECVD for thin film encapsulation.</p> <p>WONIK IPS will make continuous efforts to get the competitive edges and improvement in Korea's semiconductor & display business, by stepping up to the best level of technology through more intensified R&D.</p> |

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| Exhibit Description (Within 200 words) | Dry etcher for AMOLED, LCD and Oxide TFT - Function : TFT patterning using plasma - Application : a-Si, p-Si(LTPS), Oxide TFT - Features High etch rate & increased throughput Higher PM cycle by low power process Easy maintenance by unique chamber design PECVD for thin film encapsulation - Function : Prevent oxygen and hydrogen for AMOLED with inorganic layer - Application : Flexible OLED(SiNx, SiOx) - Features High throughput & small footprint Provide process integration know-how Secured hardware stability through advance simulation High productivity with high cleaning rate |
| Exhibit Product | Dry etcher, PECVD for thin film encapsulation |